IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A wafer processing apparatus comprising:

a chamber;

a first opening ~~portion~~ through which [[the]] gas fluidically communicates between an interior and [[the]] an exterior of the chamber ~~communicate~~; and

a door ~~that substantially closes the first opening portion~~ including a door body whose outer shape is smaller than an inner shape of said first opening so as to close said first opening and at least one projection extending from the door body,

wherein ~~the door has a projection which partially protrudes from the outer shape of the door, and when~~ in a condition where the door is positioned to ~~substantially~~ close the first opening ~~portion only~~, the projection contacts with a peripheral portion of [[the]] said first opening inside a wall of said chamber, and an aperture which gas fluidically communicates between the interior and the exterior of the chamber, still remains between the outer shape of the door body and the inner shape of said first opening ~~portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening~~.

Claim 2 (Currently Amended): A wafer processing apparatus according to claim 1, wherein the projection is provided at ~~one of four~~ each corners of the door body ~~so as to protrude toward the outside of the door~~.

Claim 3 (Canceled).

Claim 4 (Currently Amended): A wafer processing apparatus ~~including~~ according to claim 1 wherein the chamber is a part of a mini-environment portion ~~having a chamber therein and~~ used for transferring a wafer between a clean box having a lid and housing the wafer and the chamber~~, said apparatus comprising~~:

[[a]] wherein said first opening ~~portion in communication with the chamber, facing~~ faces to an opening of the clean box so as to allow loading and unloading the wafer between the clean box and the mini-environment portion; and

[[a]] said door that closes[[,]] when the transfer of the wafer is not performed, [[the]] said first opening ~~portion,~~ and opens[[,]] said first opening when the transfer of the wafer is performed[[,]]

~~wherein the door has a projection which partially protrudes from the outer shape of the door, and when the door is positioned to close the first opening portion only the projection contacts with periphery portion of the first opening portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening~~.

Claim 5 (Currently Amended): A wafer processing apparatus according to claim 4, wherein the projection is provided at ~~one of four~~ each corners of the door ~~so as~~ to protrude toward the outside of the door.

Claim 6 (Canceled).

Claim 7 (Currently Amended): A wafer processing apparatus ~~comprising~~ according to claim 1:

~~a chamber;~~

~~a first opening portion through which the interior and the exterior of the chamber communicate; and~~

~~a door that substantially closes the first opening portion,~~

wherein the ~~door has a~~ projection and the aperture ~~which is made into a shape so as to suppress~~ effect suppressing an influence on [[air]] a gas flow passing through a communication path from the interior to the exterior of the chamber ~~when~~ in a case of comparing a case that there is no projection~~, and when the door is positioned to substantially close the first opening portion only the projection contacts with periphery portion of the first opening portion, the projection provides a predetermined positional relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening~~.

Claim 8 (Currently Amended): A wafer processing apparatus according to claim 7, ~~comprising:~~

~~a chamber having a wall portion with a window opening through which wafers are received into the chamber or remove therefrom; and~~

~~a door configured to close the window opening, the door comprising a plurality of projections extending from an outermost perimeter thereof, the plurality of projections being shaped to reduce~~ wherein the influence is a gas flow turbulence generated ~~by opening and closing~~ when the door opens or closes~~, wherein, when the door is positioned to substantially close the window opening, only the plurality of projections contact a surface of the wall portion adjacent to the window opening, the projection provides a predetermined positional~~

~~relationship between the door and the first opening by contacting with a peripheral portion of the first opening, when the door substantially closes the first opening~~.

Claims 9-10 (Canceled).